

## KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[WeC2] Advanced Metrology & Inspection, Process Diagnostics & Control, and Yield	
Management IV	
Session Date	November 12 (Wed.), 2025
Session Time	14:10-15:40
Session Room	Room C (Grand Ballroom 3, 2F)

[WeC2-1] [Invited] 14:10-14:40

## **Development of DUV & EUV Optics for Semiconductor Inspection**

Hagyong Kihm (KRISS and Univ. of Science and Tech., Korea) and Jae-Hyuck Choi (KRISS, Korea)

[WeC2-2] [Invited] 14:40-15:10

## Development of a High-Brightness LaB<sub>6</sub> Electron Source and REELS(Reflection Electron Energy Loss Spectroscopy)

Takashi Ogawa, Ha Rim Lee (KRISS, Korea), Youngkwon Haam (KRISS and Chungnam Nat'l Univ., Korea), Junhyeok Hwang, Jeong Woong Lee (KRISS, Korea), and In-Yong Park (KRISS, Univ. of Science and Tech., and Chungnam Nat'l Univ., Korea)

[WeC2-3] [Invited] 15:10-15:40

Applications of High-Speed AFM for Advanced Packaging, EUV Lithography and CMP A.D. Giddings (Infinitesima Ltd., UK)